UNITED STATES PATENT AND TRADEMARK OFFICE

CERTIFICATE OF CORRECTION

PATENT NO. : 7,595,523 B2 Page 1 of 1

APPLICATION NO. : 11/707820

DATED : September 29, 2009 INVENTOR(S) : Parthasarathy et al.

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

Column 4, Line 64-67 and Column 5, Lines 1-3 reads:

"In one embodiment, for a 2mm \times 2mm die with 60 μ m high pillars, adequate stress relief is provided in a HVFET with an on-resistance of about 1 ohm utilizing a layout comprising four racetrack transistor sections separated by dummy silicon pillars, each having a pitch (y-direction) of about 13 μ m and a length (x-direction) of about 450 μ m."

It should read:

"In one embodiment, for a 2mm \times 2mm die with 60 μ m high pillars, adequate stress relief is provided in a HVFET with an on-resistance of about 1 ohm utilizing a layout comprising four racetrack transistor sections separated by dummy silicon pillars, each having a pitch (x-direction) of about 13 μ m and a length (y-direction) of about 450 μ m."

Signed and Sealed this Thirty-first Day of July, 2012

David J. Kappos

Director of the United States Patent and Trademark Office